

L Number	Hits	Search Text	DB	Time stamp
1	7892	(applied adj materials).asn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 12:02
8	53	((applied adj materials).asn.) and (passthrough pass-through passthru pass-thru)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 12:07
15	9	((applied adj materials).asn.) and ((passthrough pass-through passthru pass-thru) near20 (degas\$4 de-gas\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 12:11
22	114	(passthrough pass-through passthru pass-thru) near20 (cool\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 14:57
29	95853	(multi adj (process\$3 module chamber)) multimodule multichamber multiprocess\$3 cluster	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 12:13
36	6	((passthrough pass-through passthru pass-thru) near20 (cool\$4)) and ((multi adj (process\$3 module chamber)) multimodule multichamber multiprocess\$3 cluster)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 12:21
43	417	(loadlock\$3 (load adj lock\$3)) near20 cool\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 12:23
50	122	((loadlock\$3 (load adj lock\$3)) near20 cool\$4) and (single adj2 wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 12:23
57	148	(loadlock\$3 (load adj lock\$3)) near20 (single adj wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 13:33
64	47	((loadlock\$3 (load adj lock\$3)) near20 cool\$4) and ((loadlock\$3 (load adj lock\$3)) near20 (single adj wafer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 13:31
71	2	4,816,098.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 12:47
78	770	414/935.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 13:32

85	2751	414/935-941.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 13:32
92	126	(loadlock\$3 (load adj lock\$3)) near10 (single adj wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 13:41
99	1511	118/719.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 13:41
106	2028	29/25.01.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 13:41
113	1313	(passthrough pass-through passthru pass-thru intermediate) near20 (CVD (chemical adj vapor adj deposition))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 15:29
120	995	(passthrough pass-through passthru pass-thru intermediate) near10 (CVD (chemical adj vapor adj deposition))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 15:30
127	31	((multi adj (process\$3 module chamber)) multimodule multichamber multiprocess\$3 cluster) and ((passthrough pass-through passthru pass-thru intermediate) near10 (CVD (chemical adj vapor adj deposition)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/11 15:30